

Japan Micropatterning Committee Meeting Summary and Minutes

SEMI Japan Standards Summer 2012 Meetings
Tuesday, August 28, 2012 15:30-17:30
SEMI Japan, Tokyo, Japan

Next Committee Meeting

SEMI Japan Standards Winter 2012 Meetings
Tuesday, December 11, 2012, 15:30-17:30
SEMI Japan, Tokyo, Japan

Table 1 Meeting Attendees

Co-Chair: Iwao Higashikawa (Toshiba)

SEMI Staff: Naoko Tejima (SEMI Japan)

<i>Company</i>	<i>Last</i>	<i>First</i>	<i>Company</i>	<i>Last</i>	<i>First</i>
Toshiba	Higashikawa	Iwao	Dai Nippon Printing	Suzuki	Toshio
Toppan Printing	Otaki	Masao	SEMI Japan	Tejima	Naoko

** alphabetical order by last name*

Table 2 Leadership Changes

None

Table 3 Ballot Results

None

Table 4 Authorized Ballots

#	When	SC/TF/WG	Details
5483	C7-12	5-year-review Task Force	Reapproval of SEMI P47-0307, Test Method for Evaluation of Line-edge roughness and Line-width Roughness

Table 5 Authorized Activities

#	Type	SC/TF/WG	Details
5483	SNARF	5-year-review Task Force	Reapproval of SEMI P47-0307, Test Method for Evaluation of Line-edge roughness and Line-width Roughness
5484	SNARF	5-year-review Task Force	Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition

Note: SNARFs and TFOFs are available for review on the SEMI Web site at:

<http://downloads.semi.org/web/wstdsbal.nsf/TFOFSNARF>

Table 6 New Action Items

Item #	Assigned to	Details
MP120828-1	Mask Data Format for Mask Tools Task Force	To prepare the information (blue) ballot of Doc. 5229 by October 31
MP120828-2	5 Year Review Task Force	To draft the document of Doc. 5484 by December 31.
MP120828-3	SEMI Staff	To prepare reapproval ballot of SEMI P47.
MP120828-4	SEMI Staff	To send the documents which are due for 5-year-review (SEMI-P23, SEMI-P35, SEMI-P36) to Iwao Higashikawa, Masao Otaki and Toshio Suzuki so that they can judge whether they should be revised or not.
MP120828-5	Iwao Higashikawa, Masao Otaki and Toshio Suzuki	To review SEMI P23-0200, SEMI P35-1106, SEMI P36-1108 and discuss that they should be revised or not.

1 Welcome, Reminders and Introductions

Iwao Higashikawa, committee co-chair, called the meeting to order at 15:30. Self-introductions were made followed by the agenda review.

2 Required Meeting Elements

The meeting reminders on program membership requirement, antitrust issues, intellectual property issues and international effective meeting guidelines, were reviewed by SEMI staff, Naoko Tejima.

3 Review of Previous Meeting Minutes

The committee reviewed the minutes of the previous meeting held on April 12, 2012.

Motion: To approve the minutes of the previous meeting as written.

By / 2nd: Masako Otaki (Toppan Printing) / Toshio Suzuki (Dai Nippon Printing)

Discussion: None

Vote: 2 in favor and 0 opposed. **Motion passed.**

Attachment: 01_JA_Micropatterning_Previous_Mtg_Minutes_120828

4 SEMI Staff Report

Naoko Tejima gave the SEMI staff report. This report included SEMI Global 2012 Calendar of Events, Standards Meeting Schedule in Future, SEMI Standards Publications, A&R Summary in June 2012, 2012 Critical Dates for SEMI Standards Ballots, Highlight from Standards Meeting during SEMICON West 2012, JRSC Planning Meeting, SEMICON Japan / PVJapan 2012 and Contact Information.

Attachment: 02_SEMI_Staff_Report_120828

5 Liaison Reports

5.1 North America Microlithography Committee Report

Naoko Tejima briefly reported for the North America *Microlithography Committee*. This report included Task Force and Leadership Changes, Leadership, Current Committee Structure, Meeting Information, Document Review Summary, New Activities, Technical Ballots to be Reviewed and Task Force Updates.

Attachment: 03_NA_Microlithography_Report_August_120828

6 Task Force Reports

6.1 Mask Data Format for Mask Tools Task Force

Toshio Suzuki reported for the Mask data Format for Mask Tools Task Force. Of note:

- Task Force planned to issue the information (blue) ballot of *Doc. 5229, Revision to SEMI P44, Specification for Open Artwork System Interchange Standard (OASIS) Specific to Mask Tools*, by October 31 and to submit the letter (yellow) ballot for earlier cycle in 2013.

Action Item: Mask Data Format for Mask Tools Task Force to prepare the information (blue) ballot of Doc. 5229 by October 31

6.2 5 Year Review Task Force

Masao Otaki reported for the 5 Year Review Task Force. Of note:

- Task Force is reviewing SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition, and considering whether the item of the half-tone mask should be added or not.
- The Task Force is planning to submit the letter ballot for earlier cycle in 2013.

Motion: To approve a new SNARF to revise SEMI P22-0307.

By / 2nd: Masako Otaki (Toppan Printing) / Toshio Suzuki (Dai Nippon Printing)

Discussion: None.

Vote: 2 in favor and 0 opposed. **Motion passed.**

Attachment: 04_SNARF_of_SEMI-P22_120828

Action Item: 5 Year Review Task Force to draft the document of *Doc. 5484, Revision to SEMI P22-0307, Guideline for Photomask Defect Classification and Size Definition* by December 31.

6.3 Doc.#5483, Reapproval of SEMI P47-0307, Test Method for Evaluation of Line-edge roughness and Line-width Roughness

The SNARF of Reapproval of SEMI P47-0307 was reviewed and approved to be submitted for Cycle 7, 2012

Motion: To approve a new SNARF to reapprove SEMI P47-0307.

By / 2nd: Masako Otaki (Toppan Printing) / Toshio Suzuki (Dai Nippon Printing)

Discussion: None.

Vote: 2 in favor and 0 opposed. **Motion passed.**

Motion: To submit SEMI P47-0307 Reapproval ballot for Cycle 7, 2012.

By / 2nd: Masako Otaki (Toppan Printing) / Toshio Suzuki (Dai Nippon Printing)

Discussion: None.

Vote: 2 in favor and 0 opposed. **Motion passed.**

Action Item: SEMI Staff to prepare reapproval ballot of SEMI P47.

Attachment: 05_SNARF_of_SEMI-P47_120828

7 Old Business

7.1 Previous Meeting Action Items

Naoko Tejima reviewed the previous meeting action items.

Table 7 Previous Meeting Actions Items

<i>Item #</i>	<i>Assigned to</i>	<i>Details</i>
MP120412-1	SEMI Staff	To confirm when the latest North America Microlithography committee meeting was held. And, SEMI Staff to distribute the liaison report to the Japan Micropatterning committee TC members if needs arises. Closed
MP120412-2	Masao Otaki	To submit the SNARF for the Revision of P22 and propose the ballot submission to approve at the next Japan Micropatterning committee meeting if the TF decides that P22 should be revised. Closed
MP120412-3	SEMI Staff	To provide Masao Otaki and Iwao Higashikawa some SNARFs that they can refer to. To announce the URLs for the ballot documents in cycle 3 for their reference. Closed
MP120412-4	SEMI Staff	To prepare the SNARF for the reapproval of P47 to approve by the next Japan Micropatterning committee meeting. Closed

8 New Business

8.1 5 Year Review Documents

Naoko Tejima reported that the following documents are due for 5-year-review.

- SEMI P23-0200 (Reapproved 1107), Guidelines for Programmed Defect Masks and Benchmark Procedures for Sensitivity Analysis of Mask Defect Inspection Systems
- SEMI P35-1106, Terminology for Microlithography Metrology
- SEMI P36-1108, Guide for Magnification Reference for Critical Dimension Measurement Scanning Electron Microscopes (CD-SEMS)

Action Item: SEMI Staff to send the above documents to Iwao Higashikawa, Masao Otaki and Toshio Suzuki so that they can judge whether they should be revised or not.

Action Item: The above 3 members to review SEMI P23-0200, SEMI P35-1106, SEMI P36-1108 and discuss that they should be revised or not.

9 Action Item Review

9.1 New Action Items

Naoko Tejima reviewed the new action items. These can be found in the New Action Items table at the beginning of these minutes.

10 Next Meeting and Adjournment

The next meeting of the Japan Micropatterning Committee is scheduled for Tuesday, December 11, 2012 15:30-17:30, at SEMI Japan, Tokyo, Japan.



Respectfully submitted by:
Naoko Tejima
Manager, Standards
SEMI Japan
Phone: +81.3.3222.5804
Email: ntejima@semi.org

Minutes approved by:

Iwao Higasikawa (Toshiba), Co-chair	December, 11, 2012
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Table 8 Index of Available Attachments #1

#	<i>Title</i>	#	<i>Title</i>
1	JA_Micropatterning_Previous_Mtg_Minutes_120828	4	SNARF_of_SEMI-P22_120828
2	SEMI_Staff_Report_120828	5	SNARF_of_SEMI-P47_120828
3	NA_Micropatterning_Report_August_120828		

#1 Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact Naoko Tejima at the contact information above.